 <b>INFORMATION DISCLOSURE CITATION</b> <small>(Use several sheets if necessary)</small>				ATTY DOCKET NO. <b>14002-7</b>		SERIAL NO. <b>TBD</b>	
				Chou et al.			
				FILING <b>November 12, 2003</b>		GROUP <b>TBD</b>	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BT		4,592,081	05/27/1986	Eaton et al.			
		4,211,489	07/08/1980	Kleinknecht et al.			
		2,302,024	11/17/1942	Goss, Jr.			
		3,742,229	06/26/1973	Smith et al.			
		3,951,548	04/20/1976	Westell			
		4,037,325	07/26/1977	Weber et al.			
		4,200,395	04/29/1980	Smith et al.			
		4,475,223	10/02/1984	Taniguchi et al			
		4,588,468	05/13/1986	McGinty et al.			
↓		4,883,563	11/28/1989	Kotani et al.			
BT		6,056,526	05/02/00	Sato			
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
BT		1196749	01/30/1988	Japan w/English Abstract			
↓		244884	03/28/1986	European			
↓		4255307	09/10/1992	Japan w/English Abstract			
BT		4332694	08/05/1991	Japan w/English Abstract			
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
BT		Broers, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter</u> 33 (5), 1978 American Institute of Physics, 392-394, (September 1, 1978)					
BT		Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science</u> , Vol. 272, 85-87, (April 5, 1996)					
EXAMINER <b>Binh Tran</b>				DATE CONSIDERED <b>3/3/06</b>			

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>  <span style="font-size: 1.5em;">3-16-04</span>				ATTY DOCKET NO. <b>14002-15</b>		SERIAL NO. <b>TBD</b>	
				Chou et al.			
				FILING <b>November 12, 2003</b>		GROUP <b>TBD</b>	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
BT	5,352,394	10/04/1994	Fujita et al.				
	3,743,842	07/03/1973	Smith, H.I., et al.				
	4,310,743	01/12/1982	Seliger, R.L.				
	4,383,026	05/10/1983	Hall, T.M.				
	4,450,358	05/22/1984	Reynolds, G.O.				
	4,498,009	02/05/1985	Reynolds, G.O.				
	4,516,253	05/07/1985	Novak, W.T.				
	4,552,615	11/12/1985	Amendola, A., et al.				
J	4,576,678	03/18/1986	Shibata, H.				
	4,606,788	08/19/1986	Moran, P.L.				
BT	4,731,155	03/15/1988	Napoli, L.S., et al.				
<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
BT	9117565	11/14/1991	PCT				
BT	98/26913	06/25/1998	PCT				
BT	WO 93/21671	10/28/1993	PCT				
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
BT		Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering 11</u> , Elsevier Science Publishers B.V., 317-321, (1990)					
BT		Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter 62 (23)</u> , 1993 American Institute of Physics, 2989-2991 (June 7, 1993)					
EXAMINER <span style="font-size: 1.2em;">Binh Tran</span>				DATE CONSIDERED <span style="font-size: 1.2em;">3/3/06</span>			
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				FILING <b>December 10, 2003</b>		GROUP <b>TBD</b>	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
B5		3,833,303	09/03/1974	Burns et al.			
		4,325,779	04/20/1982	Rossetti, J.J.			
		4,832,790	05/23/1989	Rossetti, J.J.			
		5,277,749	01/11/1994	Griffith, J.H., et al.			
		5,861,113	01/19/1999	Choquette, S.J., et al.			
		5,032,216	07/16/1991	Felten			
		5,152,861	10/06/1992	Hann			
		4,664,862	05/12/1987	Ghavamikia			
		5,253,409	10/19/1993	Bier et al.			
✓		5,234,571	08/10/1993	Noeker			
B5		4,738,010	04/19/1988	Ehrfeld et al.			
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
B5		Hara, et al., "An Alignment Technique Using Diffracted Moire Signals", <u>J. Vac. Sci. Technol. B7 (6)</u> , 1989 American Vacuum Society, 1977-1979, (Nov./Dec. 1989)					
B5		Harmening, et al., "Molding of Threedimensional Microstructures by the Liga Process" <u>Proceedings IEEE: Micro Electro Mechanical Systems</u> , Travemunde, Germany, 202-207, (1992)					
EXAMINER <span style="font-size: 1.2em;">Binh Tran</span>				DATE CONSIDERED <span style="font-size: 1.2em;">3/3/06</span>			
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				Chou et al.			
				FILING November 12, 2003		GROUP TBD	

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
BT	5,119,151	06/02/1992	Onda				
↓	4,781,790	11/01/1988	Wu				
	4,788,015	11/29/1988	Sakai et al.				
	4,294,650	10/13/1981	Werthmann				
	3,923,566	12/02/1975	Law				
	5,259,926	11/09/1993	Kuwabara et al.				
	5,425,848	06/20/1995	Haisma et al.				
	5,503,963	04/02/1996	Bifano				
	4,543,225	09/24/1985	Beaujean				
BT	5,434,107	07/18/1995	Paranjpe				
BT	5,338,396	08/16/1994	Abdala et al.				

FOREIGN PATENT DOCUMENTS								
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION			
					YES	NO		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
BT		Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> 145-149, (1992)
BT		Nomura, et al., "Moire Alignment Technique for the Mix and Match Lithographic System: <u>J. Vacuum Society Technol. B6 (1)</u> , American Vacuum Society, 394-398, (Jan/Feb 1988)

EXAMINER <span style="font-size: 1.2em;">B m h Tran</span>	DATE CONSIDERED <span style="font-size: 1.2em;">3/3/06</span>
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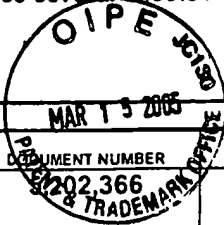








**INFORMATION DISCLOSURE CITATION**  
(Use several sheets if necessary)



Docket Number (Optional)

14002-7

Application Number

10/706,757

Applicant(s)

Stephen Y. Chou, et al.

Filing Date

November 12, 2003

Group Art Unit

1765

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BT		2002,366	04/13/93	Reid et al.	523	516	
BT		2001/0040145	11/15/01	Willson et al.	216	52	

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							Yes	No
BT		WO 02/03142	10-01-02		G03F	7/00		
BT		62214531	21-09-87		G11B	7/24		

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

BT		Schulz, et al., "Low-Temperature Wafer-Scale 'WARM' Embossing for Mix & Match with UV-Lithography", 2002, Proceedings of SPIE, Vol. 4688, pgs. 223-231	
BT		Khang, et al., "Room-temperature imprint lithography by solvent vapor treatment", February 14, 2000, Applied Physics Letters, Vol. 76, No. 7, pgs. 870-872	
		Lebib, A., et al., "Room-temperature and low-pressure nanoimprint lithography", 2002, Microelectronic Engineering, 61-62, pgs. 371-377	
		Pfeiffer, K., et al., "Suitability of new polymer materials with adjustable glass temperature for nano-imprinting", 1999, Microelectronic Engineering, 49, pgs. 431-434	
		Haisma, et al., "Mold-assisted nanolithography: A process for reliable pattern replication", Nov/Dec 1996, J. VA. Sci. Technol. B 14(6), pgs. 4124-4128	
BT		Zwiers, et al., "Aspherical lenses produced by a fast high-precision replication process using UV-curable coatings", December 15, 1985, Applied Optics, Vol. 24, No. 24, pgs. 4483-4488	

Examiner

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Date Considered

3/3/06

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Form PTO-A820 (also form PTO-1449)